

ABSTRACT OF THE DISCLOSURE

The present invention discloses a method of manufacturing an array substrate, comprising: forming an electrode line on a substrate using a wet etching technique; and forming an organic insulating layer on an exposed surface of the substrate while covering the electrode line, wherein the electrode line has a side portion having an overhang or a taper angle of more than 45°C. Due to the method, the ashing process using a dry etchant gas cannot be needed anymore.